

# Surfactants, Diffusion, and Reactivity of GaN Surfaces

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<http://www.fhi-berlin.mpg.de/th/th.html>

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## **Stoichiometry, geometry, stability, electronic structure of zincblende and wurtzite GaN**

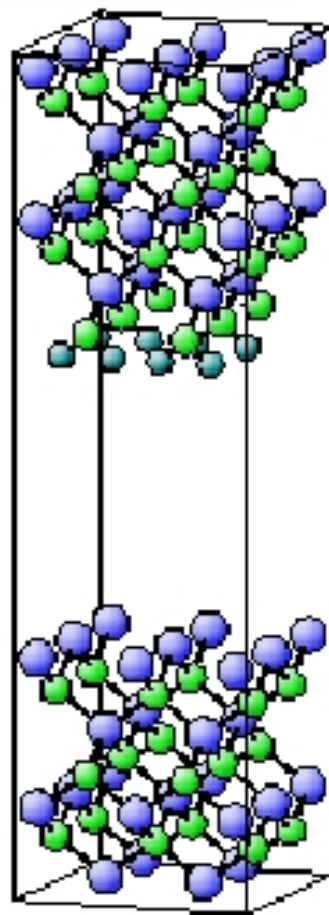
- clean surfaces
- arsenic covered surfaces
- indium covered surfaces
- surface diffusion and growth
- adsorption of oxygen

## Computational Method

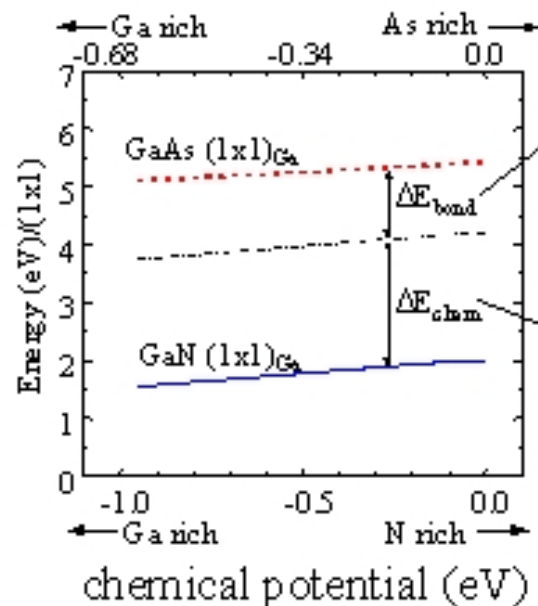
- Density-functional theory with local-density approximation for xc
- Pseudopotentials, plane-wave basis set (energy cutoff of 60 Ry)
- Ga 3d electrons treated as *valence*
- Supercell geometry
  - containing up to 180 atoms
  - passivation of one side by fractional hydrogen
  - compensation of electric field
  - atomic relaxation

code: fhi96md → fhi99md

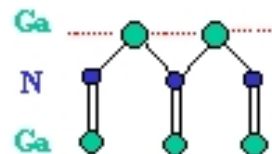
<http://www.fhi-berlin.mpg.de/th/th.html>



## Why are Ga-terminated surfaces so stable?



Stronger Ga-Ga bonding (GaN lattice constant 20% smaller than GaAs)



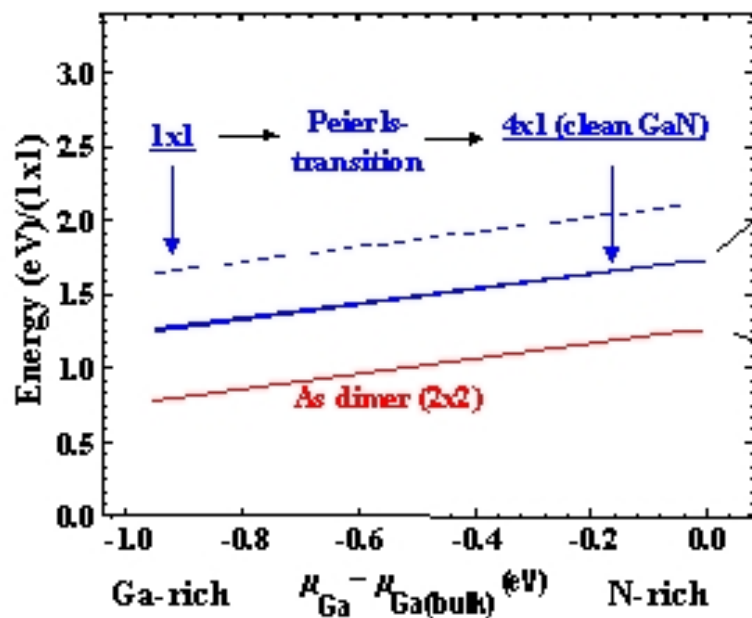
Difference in chemical potentials

Cohesive Energies:

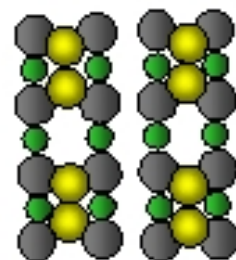
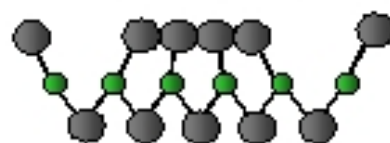
- Ga-bulk: 2.81 eV
- As-bulk: 2.96 eV
- N<sub>2</sub>-molecule: 5.0 eV

# Reconstructions and Surfactants at Cubic Surfaces

Surface Energies:

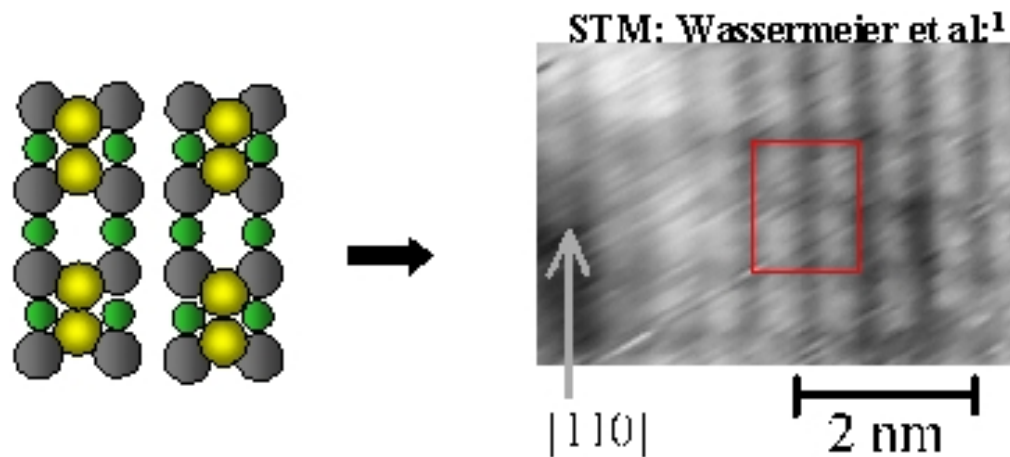


(4x1) tetramer



## Comparison with Experiment

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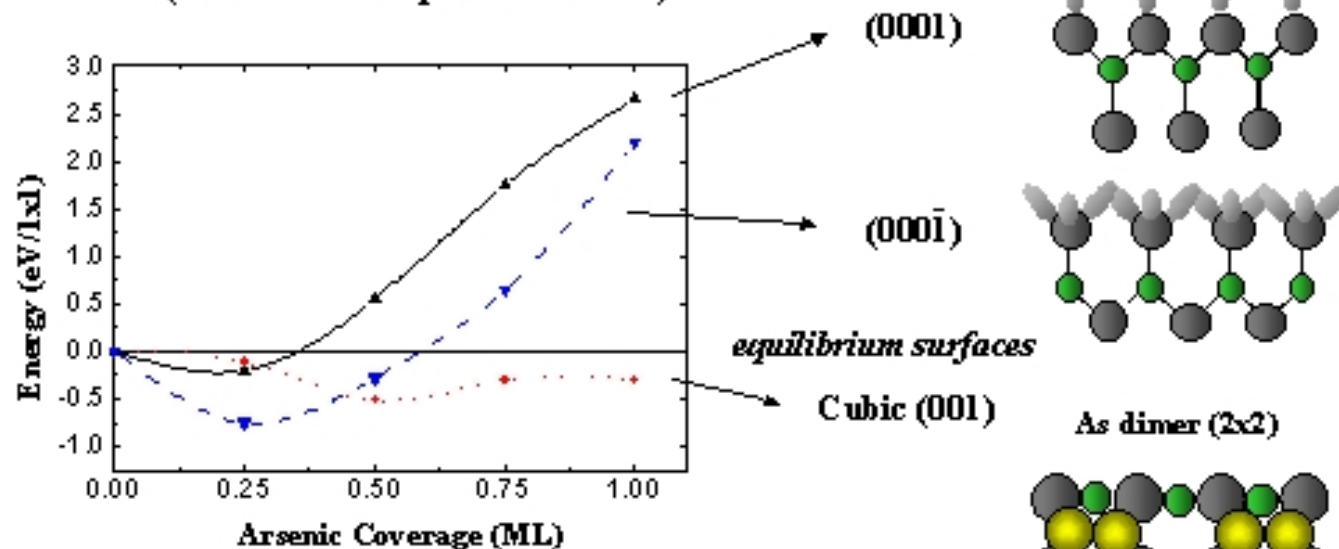


- Structure consistent with experiment
  - Arsenic is more stable on the GaN surface than in GaAs (bulk)
  - Significant reduction of the surface energy
- ➡ Arsenic (or alike) might be a good surfactant

## Surfactants at Wurtzite Surfaces?

Surface Energy (relative to clean GaN equilibrium surfaces):

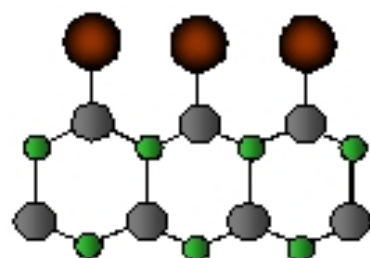
(Ga-rich and As-poor conditions)



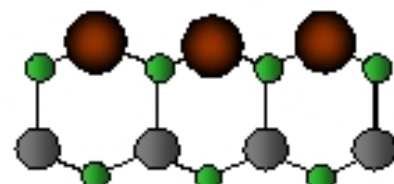
**Arsenic may be incorporated;**  
**Alternative surfactants (In, Sb)?**

# In at GaN (0001)

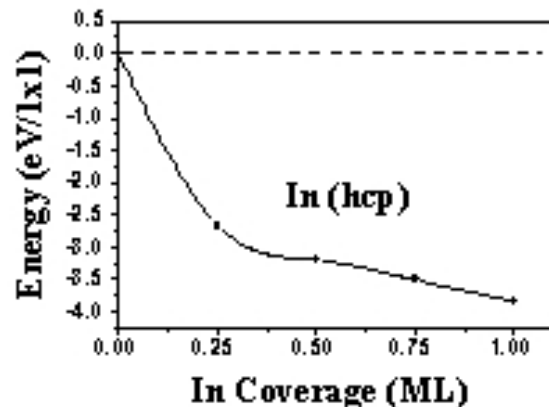
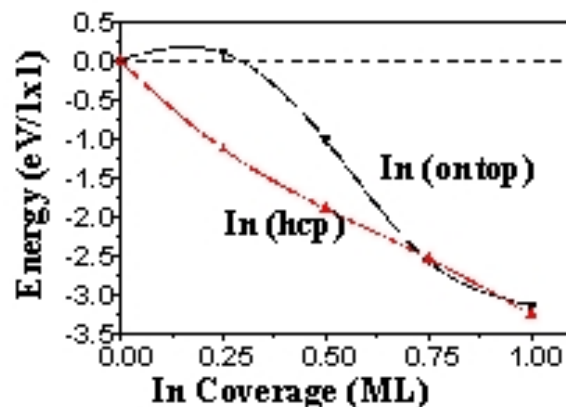
Ga terminated



N terminated



(Ga-rich conditions)



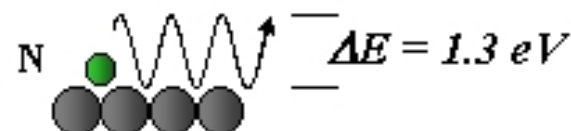
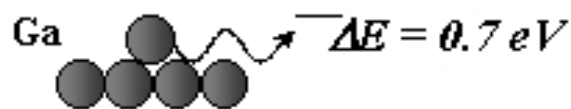
➔ In reduces significantly the surface energy

# Adatom kinetics at the clean GaN surface

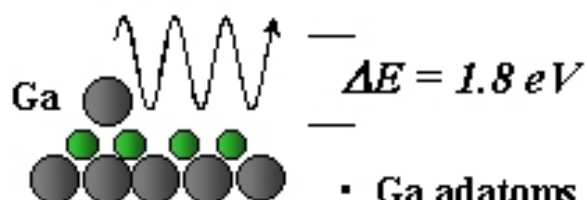
## Diffusion barriers:


Example: Ga at (0001)

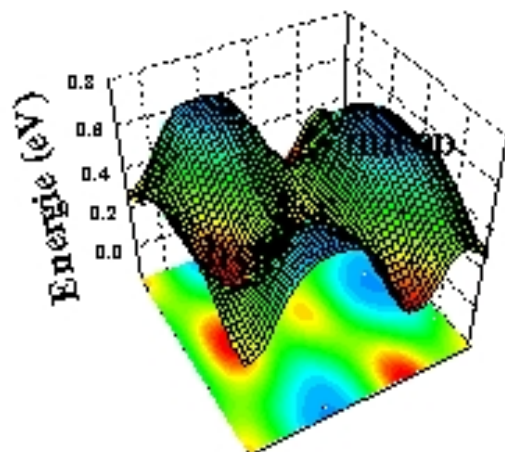
equilibrium surfaces:



kinetically stabilized surfaces:



- Ga adatoms are very mobile compared to N adatoms.
-  N terminated surfaces can be kinetically stabilized
- Excess N decreases significantly the Ga mobility!

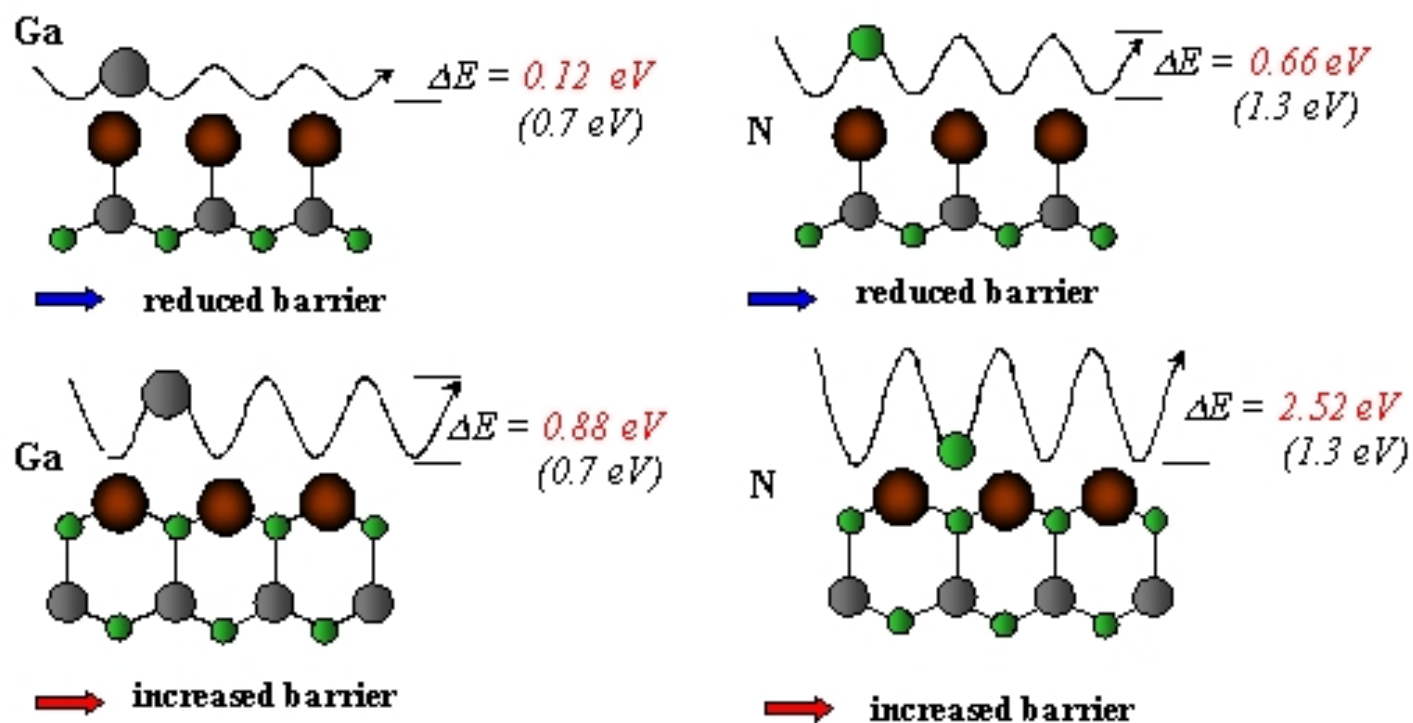


Theory: T. K. Zywicki, J. Neugebauer, M. Scheffler, *Appl. Phys. Lett.* 73, 487 (1998).

Experiment: E. J. Tarsa, B. Heying, X. H. Wu, P. Eini, S. P. DenBaars, J. S. Speck, *J. Appl. Phys.* 82, 5472 (1997).



# Adatom kinetics at In-terminated GaN (0001)



In does *not* uniformly improve adatom kinetics. More info needed: atomic exchange, what happens at steps?

## Conclusions

### Surfactants :

As- (mainly for zincblende) and In-adatoms lower the surface energy significantly.

### Surface diffusion:

- at clean GaN: Ga is fast and N is slow
- at In-covered GaN:
  - significant reduction of energy barriers for adatom diffusion when In sits above a Ga-layer.
  - However, increased barriers when indium sits above a nitrogen layer.

### Questions and plan:

What happens at steps, how can Ga replace In? Then a *predictive* kinetic Monte Carlo simulation of growth is becoming meaningful.